į

5

10

20

15

- 1. A novel structure for a photodiode comprising: a p-type region extending to the surface of a semiconductor substrate; a multiplicity of parallel finger-like n-wells formed in said p-type region that are connected to a conductive region at one end.
- The structure of Claim 1 wherein said p-type region is a p-substrate.
- The structure of Claim 1 wherein said p-type region is a p-well.
- 4. The structure of Claim 1 wherein said parallel finger-like n-wells are formed by phosphorous ion implantation.
- 5. The structure of Claim 1 wherein the depth of said parallel fingerlike n-wells is between about 1 and 5 microns.
- 6. The structure of Claim 1 wherein the width of said parallel fingerlike n-wells is between about 0.5 and 2 microns.
- 7. The structure of Claim 1 wherein the separation of said parallel finger-like n-wells is between about 0.5 and 2 microns.
- The structure of Claim 1 wherein the number of fingers in said parallel finger-like n-wells is greater than 3.
- 9. A method of fabricating a novel structure for a photodiode comprising:

Providing a p-type region of a semiconductor substrate extending to the surface of said semiconductor substrate;

The fifth of the control with the control with the control of the

ţ

5

10

15

20

- Forming a multiplicity of parallel finger-like n-wells in said p-type region that are connected to a conductive region at one end.
- 10. The method of Claim 9 wherein said p-type region is a p-substrate.
- 11. The method of Claim 9 wherein said p-type region is a p-well.
- 12. The method of Claim 9 wherein said parallel finger-like n-wells are formed by phosphorous ion implantation.
- 13. The method of Claim 9 wherein the depth of said parallel finger-like n-wells is between about 1 and 5 microns.
- 14. The method of Claim 9 wherein the width of said parallel finger-like n-wells is between about 0.5 and 2 microns.
- 15. The method of Claim 9 wherein the separation of said parallel finger-like n-wells is between about 0.5 and 2 microns.
- 16. The method of Claim 9 wherein the number of fingers in said parallel finger-like n-wells is greater than 3.
- 17. A novel structure for a photodiode comprising: an n-type region extending to the surface of a semiconductor substrate; a multiplicity of parallel finger-like p-wells formed in said n-type region that are connected to a conductive region at one end.
- 18. The structure of Claim 17 wherein said p-type region is an nsubstrate.
- 19. The structure of Claim 17 wherein said p-type region is an n-well.

The Sell of the Control of the Sell of the

U

5

10

15

20

- 20. The structure of Claim 17 wherein said parallel finger-like p-wells are formed by implantation of BF2 ions.
- 21. The structure of Claim 17 wherein the depth of said parallel fingerlike p-wells is between about 1 and 5 microns.
- 22. The structure of Claim 17 wherein the width of said parallel fingerlike p-wells is between about 0.5 and 2 microns.
- 23. The structure of Claim 17 wherein the separation of said parallel finger-like p-wells is between about 0.5 and 2 microns.
- 24. The structure of Claim 17 wherein the number of fingers in said parallel finger-like p-wells is greater than 3.
- 25. A method of fabricating a novel structure for a photodiode comprising:

Providing an n-type region of a semiconductor substrate extending to the surface of said semiconductor substrate;

- Forming a multiplicity of parallel finger-like p-wells in said n-type region that are connected to a conductive region at one end.
- 26. The method of Claim 25 wherein said n-type region is an nsubstrate.
- 27. The method of Claim 25 wherein said n-type region is an n-well.
- 28. The method of Claim 25 wherein said parallel finger-like p-wells are formed by implantation of BF2 ions.
- 29. The method of Claim 25 wherein the depth of said parallel fingerlike p-wells is between about 1 and 5 microns.

Ų

5

- 30. The method of Claim 25 wherein the width of said parallel finger-like p-wells is between about 0.5 and 2 microns.
- 31. The method of Claim 25 wherein the separation of said parallel finger-like p-wells is between about 0.5 and 2 microns.
- 32. The method of Claim 25 wherein the number of fingers in said parallel finger-like p-wells is greater than 3.